



Software solutions for optimizing micro & nano fabrication processes



# INVITATION



Thursday, 28<sup>th</sup> Feb. 2019

**Location:** HILTON HOTEL SAN JOSE, 300 Almaden Boulevard, San Jose  
**Room:** Winchester 1 & 2 (reception level)  
**Time:** 11:30 am to 5:00 pm

## Technical Open House for Lithography Simulation, Metrology and Data-Preparation Presentations and Discussion from 11:30 am to 5:00 pm

In Winchester 2 the GenISys team will be available throughout the afternoon to demo our software, answer your questions and provide direct assistance for our LAB, BEAMER, ProSEM and TRACER software packages.

In Winchester 1 we will be giving brief presentations on various basic and advanced topics for laser, e-beam, optical projection, and optical proximity lithography.

The sessions are free of charge and do not require conference registration. Light food and coffee/drinks will be provided. For registration just send a short e-mail to Roger McCay ([mccay@genisys-gmbh.com](mailto:mccay@genisys-gmbh.com)), or just drop in at any time to see the latest from GenISys.

If you have colleagues who may be interested, please forward this information on to them.

We are looking forward to sharing our product news with you and helping you with your lithography applications.

Please visit our booth #322 on the exhibition floor, Tuesday and Wednesday.

Thank you.

The GenISys Team

**GenISys Sessions**  
Winchester Room  
Hilton Hotel

